

Ground- and Excited-State Impurity Bands in Silicon Inversion Layers

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Impurities in silicon inversion layers have been the subject of considerable experimental and theoretical interest. The main purpose of this investigation is to extend the recent work on ground charged impurities in n-type Si inversion layers to the case of the lowest excited states. We show that, with the effects of disorder and for given impurity concentrations, binding energies and electric fields of interest, the lowest excited band would play an essential role in the optical and transport measurements.

I. Theory

Theoretical investigations of the ground- and excited-state impurity bands in inversion layers of metal-oxide-semiconductor (MOS) structures are important for the design and the interpretation of experiments^[1,2].

In wake of a recent work^[1], we present a thorough analysis of the ground and excited states in these structures.

The system can be described by the Hamiltonian

$$H = E_{\lambda}^B \sum_i a_i^{\dagger} a_i + \sum_{i \neq j} V_{ij} a_i^{\dagger} a_j, \quad (1)$$

where the creation annihilation operator a_i^{\dagger} (a_i) describes an electron bound to the ground (excited) state of a single impurity at site i . E_{λ}^B is the binding energy, which is taken as our reference energy below the edge of the unperturbed first conduction band (UFCB), λ are the states to be considered, and V_{ij} is the hopping

energy integral.

The states are described by the wave functions^[1]

$$\psi_{\lambda}(\vec{R}z) = \phi_{\lambda}(\vec{R})\varphi(z), \quad (2)$$

where $\vec{R} = \vec{R}(x, y)$, and

$$\phi_{2p_0}(R) = (a_0^2/2\pi)^{1/2} \exp(-a_0 R/2) \quad (3)$$

represents the surface ground state,

$$\phi_{3d\pm 1}(R) = (a_1^4/12\pi)^{1/2} (x \pm iy) \exp(-a_1 R), \quad (4)$$

represents the lowest excited state, and

$$\varphi(z) = (b^3/2)^{1/2} \exp(-bz) \quad (5)$$

is the lowest electric subband. The variational parameters a_0 , a_1 and b will be determined by minimizing the value of the Hamiltonian, calculating the energies

$$E_{\lambda} = \langle \psi_{\lambda}(R, z) | -\nabla_R^2 - \nu \nabla_z^2 + \frac{\delta}{z} + \epsilon z - 2\Phi(\vec{r}) | \psi_{\lambda}(R, z) \rangle \quad (6)$$

In this equation ϵ is the external electric field, $\Phi(\vec{r})$, $\vec{r} = \vec{r}(x, y, z)$, is the screened Coulomb potential energy $\Phi(r) = \Phi(\vec{r}, s, z_0)^{[1-3]}$ produced by the impurity

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within the oxide on the inversion layer electron, s is the screening parameter, and z_0 is the distance between the external charged and the $S_i - SiO_2$ interface. E and ν are related to the dielectric constants and the effective masses respectively^[1]. The E_λ^B is obtained from the relation^[1-3]

$$E_\lambda^B = E_0 - E_\lambda \quad , \quad \lambda = 2p_0, 3d_{\pm 1} \quad , \quad (7)$$

where E_0 is the expectation value of H without the impurity term. The hopping matrix is

$$V_{ij} = \langle \psi_i^\lambda(\vec{R}, z) | \phi(\vec{r}) | \psi_j^\lambda(R, z) \rangle \quad . \quad (8)$$

The density of states is given by

$$D(E) = -\frac{1}{\pi} \text{Im} \frac{1}{N} \sum_i G_{ii}(E + i0^+) \quad , \quad (9)$$

where $\langle G_{ii} \rangle$ is the retarded single-particle propagator averaged on the impurities configuration^[1,3,4]. We calculated $D(E)$ through the relations

$$\langle G_{ii}(E + i0^+) \rangle = \xi(E)/E \quad , \quad (10)$$

and

$$\eta(E) = \frac{N_{0x} \xi(E)}{(2\pi)^2 E^2} \int \frac{V^2(\vec{k}) d^2 k}{1 - N_{0x} \xi(E)/EV(\vec{k})} \quad . \quad (11)$$

Looking at Eq. (11), we see that we need $V(\vec{k})$, which is the Fourier transform of the hopping matrix V_{ij} . We can find, after some manipulation, that $V(\vec{k})$ can give all the information about the system to be considered. We obtain

$$V_\lambda(\vec{k}) = -(E_\lambda^B + q^2) \phi_\lambda^2(q) a^{*2} R_y^* \quad , \quad \vec{k} = \vec{q}/a^* \quad . \quad (12)$$

Then:

$$V_{2p_0} = -\frac{(E_{2p_0}^B + a^{*2} k^2) \pi}{2a_0^2 \left(\frac{1}{4} + \frac{k^2 a^{*2}}{a_0^2} \right)^3} [a^{*2} R_y^*] \quad (13)$$

and

$$V_{3d_{\pm 1}}(k) = -(E_{3d_{\pm 1}}^B + a^{*2} k^2) \pi \left\{ \frac{1}{3a_1^2 F(\vec{k})^3} \left[\frac{9}{16F(\vec{k})^2} - \frac{6}{4F(\vec{k})} + 1 \right] \right\} \quad (14)$$

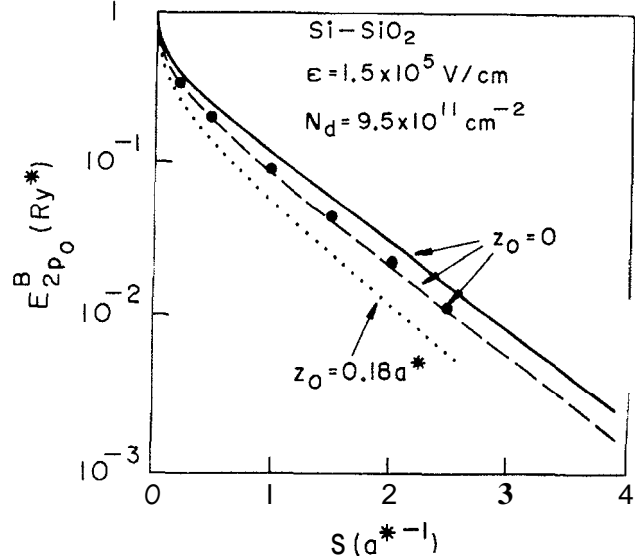


Figure 1. Binding energy of the $2p_0$ state as a function of the screening parameter. Full and dashed lines correspond to a: separable potential approximation and a modified Thomas-Fermi approximation respectively, calculated with the Klauder's multiple-scattering scheme^[5]. The big and small dots are results of our calculations.

where

$$F(\vec{k}) = \left(\frac{1}{4} + \frac{k^2 a^{*2}}{a_1^2} \right) \quad (15)$$

and $a^* = 21.8 \text{ \AA}$ and $R_y^* = 42.3 \text{ meV}$

II. Results

The binding energy for $2p_0$ state is shown in Fig.1, for specific electric field and depletion concentration N_d , and as a function of screening. The results are compared to recent results with Klauder's multiple-scattering approach^[5]. In Fig. 2 we show the Fourier transform for $2p_0$ and $3d_{\pm 1}$ states for $s = 0$ and $z_0 = 0$.

At high electric field $\epsilon \geq 10^{10} \text{ esm} = 3 \times 10^{12} \text{ V/cm}$, we find that, $E_{2p_0}^B \rightarrow 4R_y^*$ and $E_{3d_{\pm 1}}^B \rightarrow 4/9 R_y^*$. If we let $\vec{k} \rightarrow 0$ in Eqs. 13 and 14, $V_{2p_0}(\vec{k} = 0) \rightarrow V_{1s}(\vec{k} = 0)$, and $V_{3d_{\pm 1}}(\vec{k} = 0) \rightarrow V_{2s}(\vec{k} = 0)$. Both systems go to the 1s and 2s states respectively, in the ideally two-dimensional systems, as obtained by Ghazali et al^[6].

In Fig. 3 we show the density of states for $2p_0$ and $3d_{\pm 1}$ bands for different electric-fields and depletion concentrations, with $s = 0$ and $z_0 = 0$. The impurity concentration present in the $S_i - SiO_2$ inversion layer is

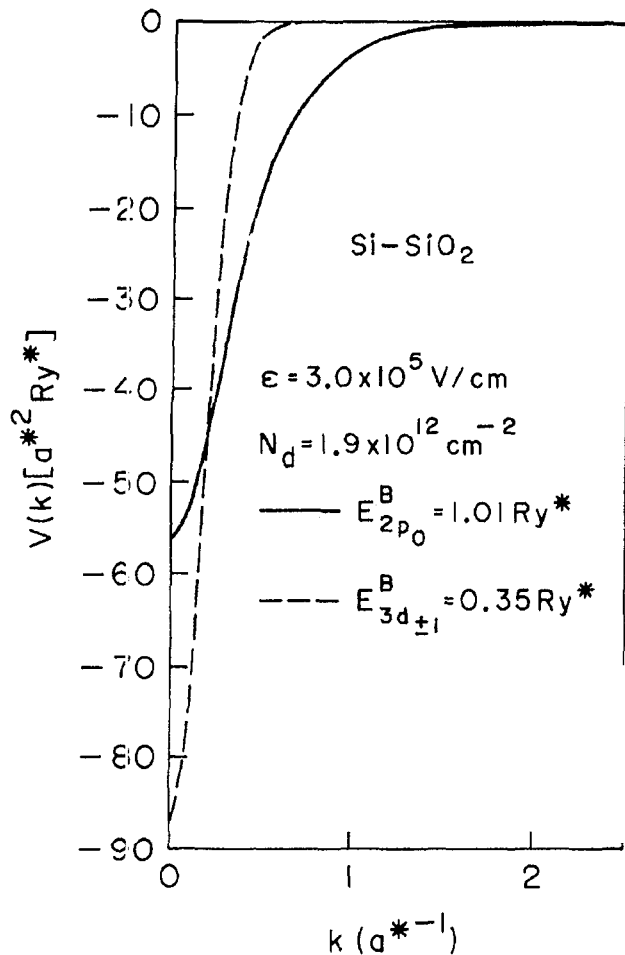


Figure 2. Fourier transform of the hopping energy for the surface ground state $2p_0$ and the lowest excited state $3d_{\pm 1}$.

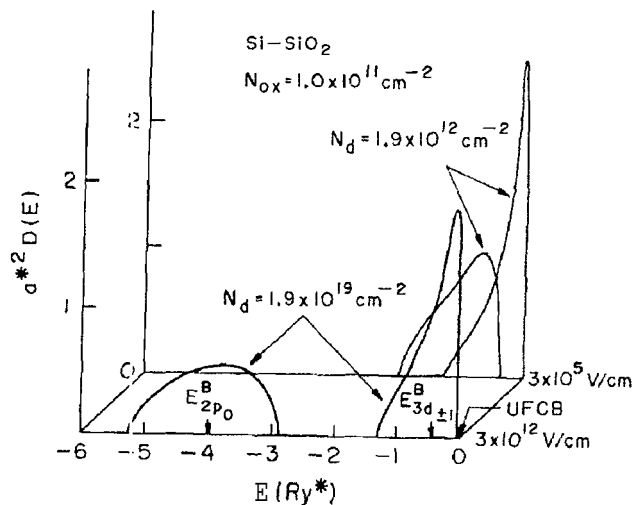


Figure 3. The calculated density of states for the $2p_0$ and $3d_{\pm 1}$ bands for two different electric-fields present in the Si-SiO_2 inversion layer. The origin is set at the unperturbed first conduction band (UFCB) and $s = 0$ and $z_0 = 0$.

$N_{ox} = 1 \times 10^{11} \text{cm}^{-1}$. The impurity bands for high electric field go to the ideally 2D separated bands^[5,7]. The results can be compared to the 1s and 2s 2D states obtained by da Cunha Lima and Ferreira da Silva^[7] and observed by Hartstein and Fowler^[2,8]. The effects of correlation^[9,10], screening and distance to the interface on the impurity bands are subject of current investigations and will appear elsewhere.

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